

L Number	Hits	Search Text	DB	Time stamp
-	161	(atomic adj layer adj deposition) with (reactor chamber apparatus)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 09:51
-	232	(ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 10:33
-	100	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) and adsorb\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 09:53
-	99	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) and adsorb\$3) and (substrates wafers)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 09:53
-	3	6042652.URPN.	USPAT	2003/02/25 10:08
-	56	("4058430" "4389973" "4413022" "4416933" "4533410" "4533820" "4689247" "4828224" "4836138" "4846102" "4867952" "4907862" "4913929" "4975252" "4976996" "4993360" "5000113" "5015503" "5077875" "5078851" "5119760" "5156820" "5194401" "5204314" "5270247" "5281274" "5294778" "5304247" "5320680" "5336327" "5484484" "5582866" "5616208" "5693139" "5702530" "5711811" "5749974" "5788447" "5851849" "5876503" "5879459" "5916365" "5935338" "6007330" "6015590" "6042652" "6050216" "6077775" "6090442" "6124158" "6139700" "6143659" "6174377" "6200893" "6270572" "6305314" "2001/0045187").PN.	USPAT	2003/02/25 10:08
-	1	((ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus)) and ((wafer substrate) with boat)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 10:37
-	124	(ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 10:59
-	351	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) or ((ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 10:59
-	69	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) or ((ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus)) and first with pressure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 11:00
-	11	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) or ((ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus)) and first with pressure) and (third with pressure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 11:01
-	3	((ald (atomic adj layer adj deposition)) with (reactor chamber apparatus)) or ((ale (atomic adj layer adj epitaxy)) with (reactor chamber apparatus)) and first with pressure) and (third with pressure) with lower	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/25 11:01